

Docket Number: 081468-0309023
Client Reference: P-1843.000-US

DFW
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

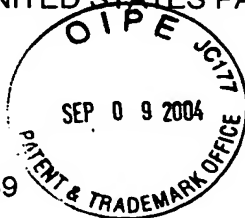
In Re the Application of

COX et al.

Application No.: 10/816,189

Filed: April 2, 2004

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD



Group Art Unit: 1756

Examiner: Unassigned

Confirmation No.: 7516

September 9, 2004

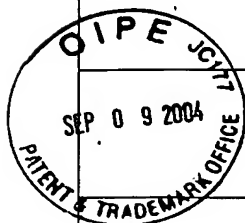
INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

| Examiner's Initials | First Inventor | Application No. | Filing Date | Enclosed |
|---------------------|--------------------------------------|-----------------|-------------|--|
| | DE SMIT (081468-0309173) | 10/820,227 | 04/08/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | DE SMIT (081468-0309978) | 10/860,662 | 06/04/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | DUINEVELD et al. (081468-0308101) | 10/773,461 | 02/09/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | FLAGELLO et al. (081468-0302644) | 10/698,012 | 10/31/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | DE SMIT et al. (081468-0306530) | 10/705,804 | 11/12/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | LOF et al. (081468-0306781) | 10/705,805 | 11/12/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | LOF et al. (081468-0306524) | 10/705,783 | 11/12/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |



| Examiner's Initials | First Inventor | Application No. | Filing Date | Enclosed |
|---------------------|--|-----------------|-------------|--|
| | VAN SANTEN et al. (081468-0307331) | 10/743,271 | 12/23/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | MULKENS et al. (081468-0307333) | 10/743,266 | 12/23/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
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| | BLEEKER (081468-0306527) | 10/715,116 | 11/18/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | STREEFKERK et al. (081468-0306882) | 10/719,683 | 11/24/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
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| | SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1) | 10/367,910 | 02/19/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input type="checkbox"/> Other: stamped receipt card |
| | HOOGEN DAM et al. (081468-0308674) | 10/831,370 | 04/26/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | STREEFKERK et al. (081468-0309421) | 10/844,575 | 05/13/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | STREEFKERK et al. (081468-0309796) | 10/850,451 | 05/21/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

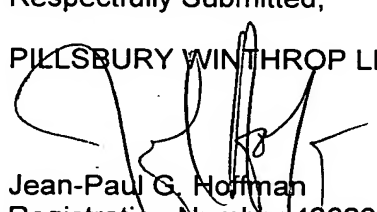
Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) **PLEASE RETURN A COPY OF THIS LETTER** with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

Secondly, please consider each document which is listed on the attached Form PTO-1449 and return a copy of that form with the Examiner's initials adjacent each citation, a copy of each document enclosed except for any U.S. patents and published patent applications. It is respectfully requested that these documents listed on the Form PTO-1449 be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

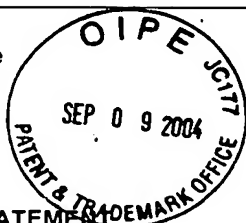
Respectfully Submitted,

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|----------------------------|--------|----------------------|
| Atty. Dkt. No. | M# | Client Ref. |
| | 309023 | P-1843.000-US |
| Applicant: COX et al. | | |
| Appln. No. 10/816,189 | | |
| Filing Date: April 2, 2004 | | |
| Examiner: Unknown | | Group Art Unit: 1756 |

INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

Date: September 9, 2004 Page 1 of 4

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Examiner: Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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|--|-----|---|-----------------|---|-------------------------|----------------------------------|---------------------------------|-------------------------------------|----|
| FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office | | | | Atty. Dkt. No. | M# 309023 | Client Ref. P-1843.000-US | | | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | | | Applicant: COX et al. | | | | | |
| | | | | Appln. No. 10/816,189 | | | | | |
| | | | | Filing Date: April 2, 2004 | | | | | |
| | | | | Examiner: Unknown | | Group Art Unit: 1756 | | | |
| Date: September 9, 2004 Page 2 of 4 | | | | | | | | | |
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| FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office | | | | | Atty. Dkt. No. | M# | Client Ref. | |
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| Date: September 9, 2004 Page <u>3</u> of <u>4</u> | | | | | | | | |
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| *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant. | | | | | | | | |

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty.
Dkt. No.

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**INFORMATION DISCLOSURE STATEMENT
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Applicant: COX et al.

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Page 4 of 4

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Group Art Unit: 1756

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Examiner

Date Considered:

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